

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|---------------------|
| L1 | 3790 | 438/257.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:23 |
| L2 | 3681 | 1 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:24 |
| L3 | 119 | 2 and (gate near electrode) and (source near electrode) and (drain near electrode) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:25 |
| L4 | 900 | 438/259.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:25 |
| L5 | 886 | 4 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:25 |
| L6 | 97 | 5 and (gate near electrode) and (source near electrode) and (drain near electrode) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:25 |
| L7 | 347 | 438/263.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |

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| L8 | 343 | 7 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L9 | 12 | 8 and (gate near electrode) and (source near electrode) and (drain near electrode) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L10 | 329 | 438/265.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L11 | 317 | 10 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L12 | 6573 | 257/314-316.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L13 | 6184 | 12 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:26 |
| L14 | 410 | 13 and (gate near electrode) and (source near electrode) and (drain near electrode) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:27 |
| L15 | 1462 | 257/324.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:28 |

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|-----|-------|---|---|----|----|---------------------|
| L16 | 1400 | 15 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:28 |
| L17 | 14481 | (method) with (semiconductor near packag\$3) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:29 |
| L18 | 43704 | (method) with ((field- effect near transistor) (field near effect near transistor) (tft)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:30 |
| L19 | 11045 | 18 and (gate near electrode) and (source near electrode) and (drain near electrode) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:30 |
| L20 | 10655 | 19 and (substrate wafer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:30 |
| L21 | 27 | 1 and 20 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/06/15 16:30 |
| S1 | 31356 | ((silicon near oxynitride) (silicon near oxy-nitride) (sion)) and (cvd or ald or chemical near vapor near deposition or atomic near layer) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/04/23 10:42 |

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|----|----|--|---|----|----|---------------------|
| S2 | 23 | ((cvd) (chemical near vapor near deposition)) and ((silicon near oxynitride) (silicon near oxy-nitride) (sion)) and ((chlorosilane) (chlor\$1 near3 silane) (dichlorosilane) (hexachlorosilane) (trichlorosilane)) and (oxidiz\$3 oxygen) and (nitrid\$3 nitrogen)).clm. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/04/23 10:45 |
| S5 | 3 | S4 and (excitation near period) and (exciting near mechanism) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/04/23 10:50 |
| S6 | 4 | "6342133".pn. "4874493".pn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/05/02 19:15 |

6/ 15/ 2009 4:32:30 PM

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